Electronic Supplementary Material (ESI) for Journal of Materials Chemistry


**Supporting Information**

# Controlled Evaporative Self-Assembly of Hierarchically Structured Bottlebrush Block Copolymer with Nanochannels

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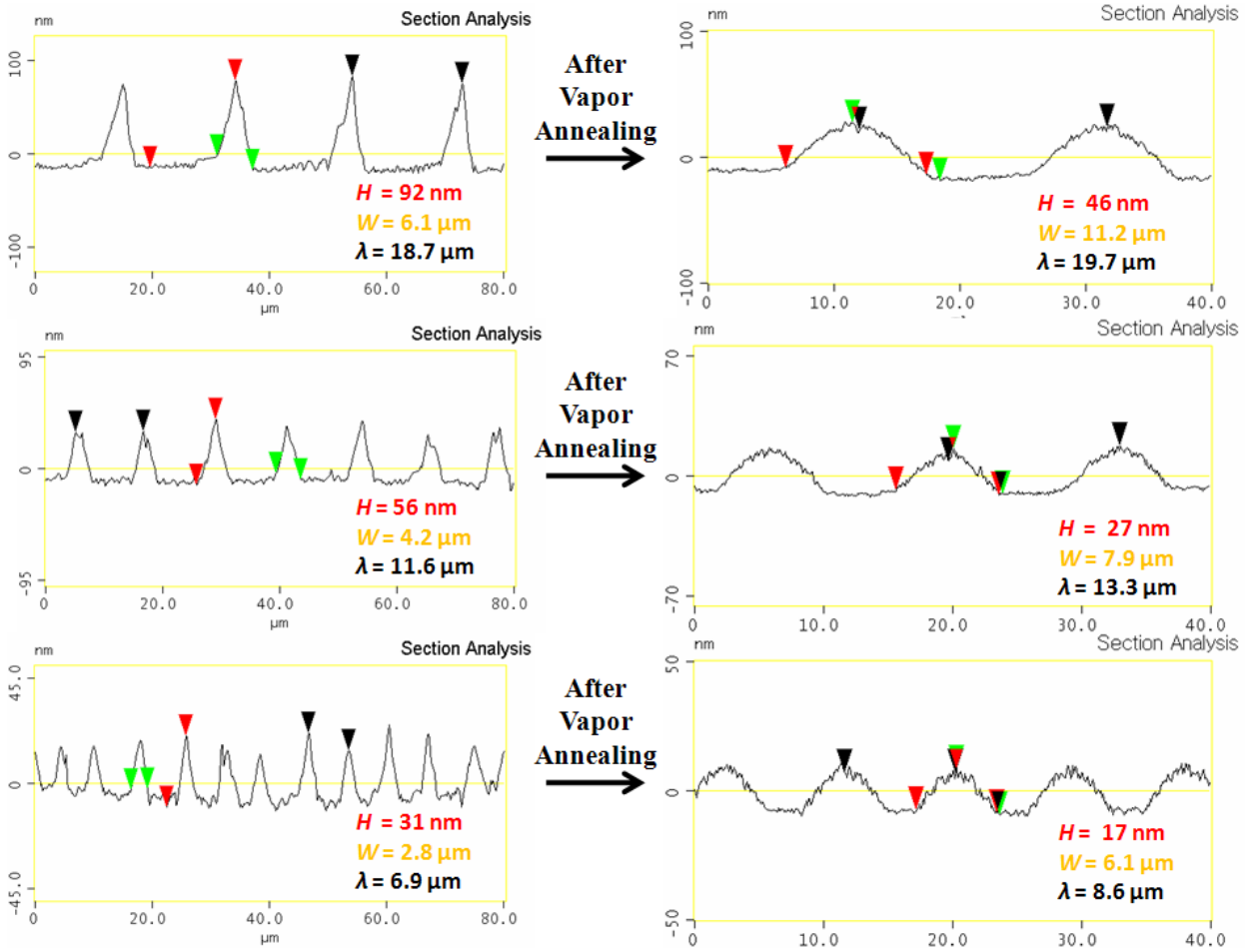


**Figure S1.** The cross-sectional view of AFM images shows the morphological evolution of the stripe height, *H*, stripe width, *W*, and the spacing between adjacent stripes, $\lambda$ of PS-PLA stripes before and after the chloroform vapor annealing. The first, second, and third rows correspond to stripes taken in the outermost region, intermediate region, and innermost region, respectively.

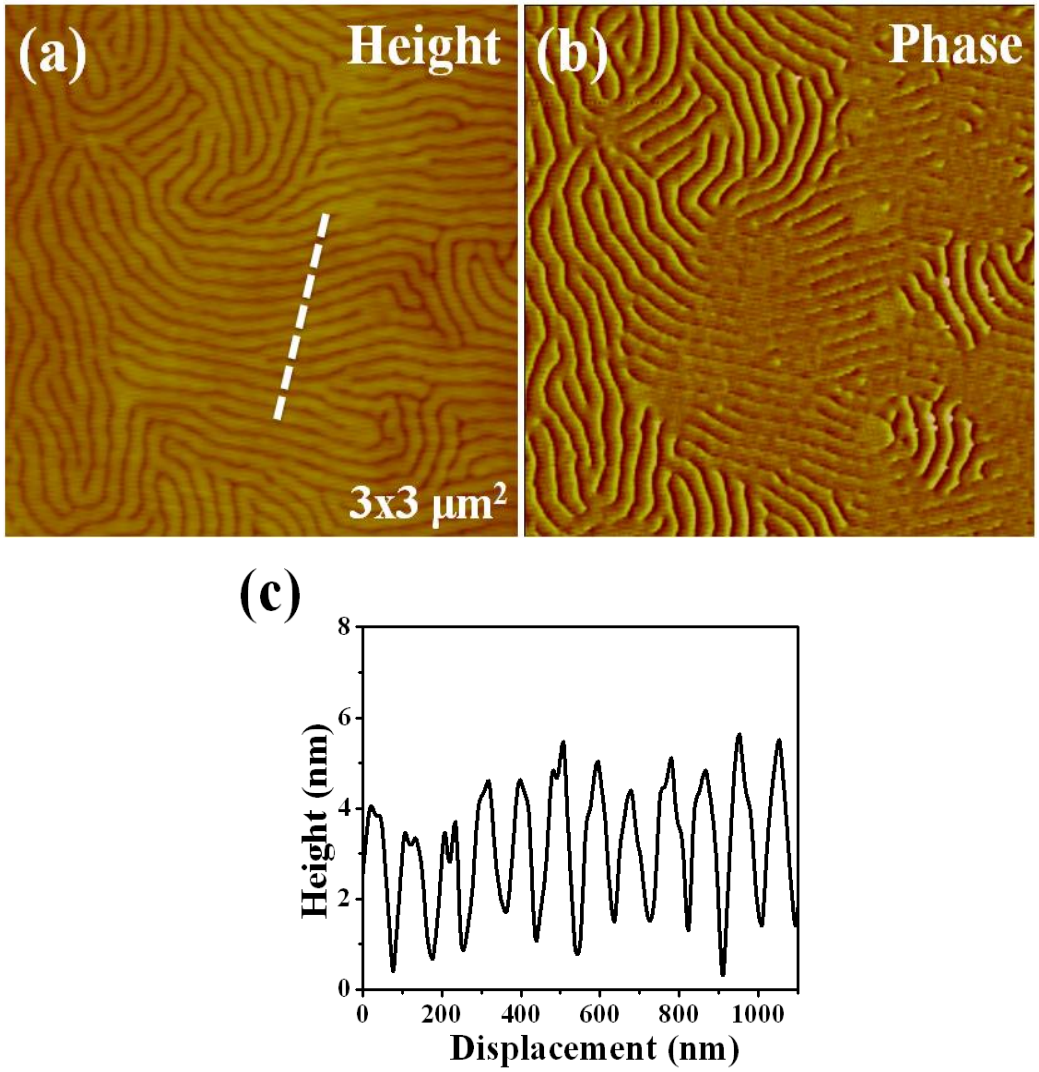


**Figure S2.** (a) AFM height and (b) phase images of lamellar morphology of PS-PLA within a stripe after the vapor annealing. (c) The cross-section analysis of the surface PS-PLA, corresponding to the white line labeled in (a). The average domain spacing, $L_0$ = 105 ± 5 nm, measured from the cross-section analysis in (c). Image size = 3μm x 3μm. Z range of the height image = 60nm.

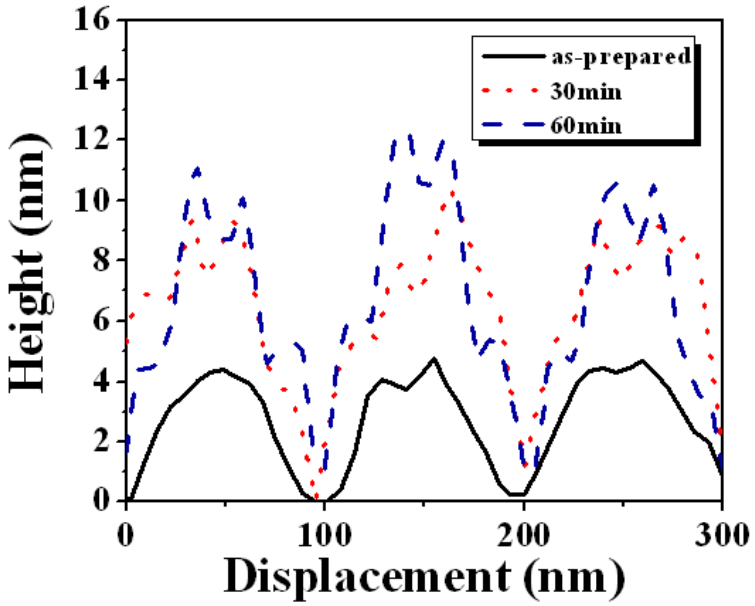


**Figure S3.** The height profiles for the AFM images shown in Figure 5, corresponding to different degradation times (i.e., as-prepared, 30min and 60min). The nanochannel depth increased with increased degradation time, which is indicative of the successful removal of PLA arms.